

## Search Results

BROWSE

SEARCH

IEEE XPLORE GUIDE

SUPPORT

Results for "((( (semiconductor)&lt;in&gt;metadata ) &lt;and&gt; ((manufacturing)&lt;in&gt;metadata ) )&lt;and&gt;g..."

Your search matched 22 of 937 documents.



A maximum of 100 results are displayed. 25 to a page, sorted by Relevance in Descending order.

New [Beta]  
Application  
Notes  
Available  
SIGNALSPEC

## Search Options

[View Session History](#)[New Search](#)

## Key

IEEE JNL	IEEE Journal or Magazine
IET JNL	IET Journal or Magazine
IEEE CNF	IEEE Conference Proceeding
IET CNF	IET Conference Proceeding
IEEE STD	IEEE Standard

Modify Search

((( (semiconductor)&lt;in&gt;metadata ) &lt;and&gt; ((manufacturing)&lt;in&gt;metadata ) )&lt;and&gt; (simul

Search &gt;

☐ Check to search only within this results setDisplay Format: ☒ Citation ☐ Citation & Abstract

IEEE/ET Books Educational Courses Application Notes [Beta]

Interactive online content developed from IEEE conference tutorials.

☐ view selected items | [Select All](#) [Deselect All](#)

- ☐ 1. **Simulation of arsenic in situ doping with polysilicon CVD and its application to high aspect ratio trenches**  
Heitzinger, C.; Pyka, W.; Tamaoki, N.; Takase, T.; Ohmine, T.; Selberherr, S.;  
[Computer-Aided Design of Integrated Circuits and Systems](#). IEEE Transactions on  
Volume 22, Issue 3, March 2003 Page(s):285 - 292  
Digital Object Identifier 10.1109/TCAD.2002.807879  
[AbstractPlus](#) | [References](#) | Full Text: [PDF](#)(409 KB) IEEE JNL  
[Rights and Permissions](#)
- ☐ 2. **The economic impact of choosing off-line, inline or in situ metrology deployment in semiconductor manufacturing**  
Spanos, C.J.; Julia, P.; Leachman, R.C.;  
[Semiconductor Manufacturing Symposium, 2001 IEEE International](#)  
8-10 Oct. 2001 Page(s):37 - 40  
Digital Object Identifier 10.1109/ISSM.2001.962909  
[AbstractPlus](#) | Full Text: [PDF](#)(336 KB) IEEE CNF  
[Rights and Permissions](#)
- ☐ 3. **Internal model control approach to run-to-run control for semiconductor manufacturing**  
Advikolanu, S.; Zafiriou, E.;  
[American Control Conference, 1997. Proceedings of the 1997](#)  
Volume 1, 4-6 June 1997 Page(s):145 - 149 vol.1  
Digital Object Identifier 10.1109/ACC.1997.611772  
[AbstractPlus](#) | Full Text: [PDF](#)(496 KB) IEEE CNF  
[Rights and Permissions](#)
- ☐ 4. **AEMPES: an expert system for in-situ diagnostics and process monitoring**  
Chen, S.-s.;  
[Semiconductor Manufacturing Science Symposium, 1990. ISMSS 1990. IEEE/SEMI International](#)  
21-23 May 1990 Page(s):119 - 122  
Digital Object Identifier 10.1109/ISMSS.1990.66129  
[AbstractPlus](#) | Full Text: [PDF](#)(340 KB) IEEE CNF  
[Rights and Permissions](#)

- ☐ **5. Process control system for VLSI fabrication**  
 Sachs, E.; Guo, R.-S.; Ha, S.; Hu, A.;  
[Semiconductor Manufacturing, IEEE Transactions on](#)  
 Volume 4, [Issue 2](#), May 1991 Page(s):134 - 144  
 Digital Object Identifier 10.1109/66.79725  
[AbstractPlus](#) | [Full Text: PDF\(1060 KB\)](#) [IEEE JNL](#)  
[Rights and Permissions](#)
- 
- ☐ **6. Development of a hexagonal-shaped rapid thermal processor using a vertical tube**  
 Byung Jin Cho; Vandenabeele, P.; Maex, K.;  
[Semiconductor Manufacturing, IEEE Transactions on](#)  
 Volume 7, [Issue 3](#), Aug. 1994 Page(s):345 - 353  
 Digital Object Identifier 10.1109/66.311338  
[AbstractPlus](#) | [Full Text: PDF\(680 KB\)](#) [IEEE JNL](#)  
[Rights and Permissions](#)
- 
- ☐ **7. Cost and cycle time performance of fabs based on integrated single-wafer processing**  
 Wood, S.C.;  
[Semiconductor Manufacturing, IEEE Transactions on](#)  
 Volume 10, [Issue 1](#), Feb. 1997 Page(s):98 - 111  
 Digital Object Identifier 10.1109/66.554493  
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(504 KB\)](#) [IEEE JNL](#)  
[Rights and Permissions](#)
- 
- ☐ **8. A simulation study of copper reflow characteristics in vias**  
 Friedrich, L.J.; Dew, S.K.; Brett, M.J.; Smy, T.;  
[Semiconductor Manufacturing, IEEE Transactions on](#)  
 Volume 12, [Issue 3](#), Aug. 1999 Page(s):353 - 365  
 Digital Object Identifier 10.1109/66.778203  
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(1136 KB\)](#) [IEEE JNL](#)  
[Rights and Permissions](#)
- 
- ☐ **9. Production data based optimal etch time control design for a reactive ion etching process**  
 Liamanond, S.; Si, J.; Yuan-Ling Tseng;  
[Semiconductor Manufacturing, IEEE Transactions on](#)  
 Volume 12, [Issue 1](#), Feb. 1999 Page(s):139 - 147  
 Digital Object Identifier 10.1109/66.744535  
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(232 KB\)](#) [IEEE JNL](#)  
[Rights and Permissions](#)
- 
- ☐ **10. Comparing the economic impact of alternative metrology methods in semiconductor manufacturing**  
 Julia, P.; Spanos, C.J.; Leachman, R.C.;  
[Semiconductor Manufacturing, IEEE Transactions on](#)  
 Volume 15, [Issue 4](#), Nov. 2002 Page(s):454 - 463  
 Digital Object Identifier 10.1109/TSM.2002.804909  
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(431 KB\)](#) [IEEE JNL](#)  
[Rights and Permissions](#)
- 
- ☐ **11. Carbon nanotube applications in microelectronics**  
 Hoenlein, W.; Kreupl, F.; Duesberg, G.S.; Graham, A.P.; Liebau, M.; Seidel, R.V.; Unger, E.;  
[Components and Packaging Technologies, IEEE Transactions on](#) [Free also Components, Packaging, and Manufacturing Technology, Part A: Packaging Technologies, IEEE Transactions on](#)  
 Volume 27, [Issue 4](#), Dec. 2004 Page(s):629 - 634  
 Digital Object Identifier 10.1109/TCAPT.2004.838876  
[AbstractPlus](#) | [Full Text: PDF\(1728 KB\)](#) [IEEE JNL](#)  
[Rights and Permissions](#)

- ☐ **12. Programmable factory IC manufacturing for the 21st century**  
K.C. Saraswat;  
[Semiconductor Manufacturing Science Symposium, 1993. ISMSS 1993., IEEE/SEMI International 1993](#) Page(s):2 - 6  
Digital Object Identifier 10.1109/ISMSS.1993.263709  
[AbstractPlus](#) | Full Text: [PDF](#)(548 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **13. Run-to-run process control for chemical mechanical polishing in semiconductor manufacturing**  
Da, L.; Kumar, V.G.; Tay, A.; Al Mamun, A.; Weng Khuen Ho; See, A.; Chan, L.;  
[Intelligent Control, 2002. Proceedings of the 2002 IEEE International Symposium on](#)  
27-30 Oct. 2002 Page(s):740 - 745  
Digital Object Identifier 10.1109/ISIC.2002.1157854  
[AbstractPlus](#) | Full Text: [PDF](#)(617 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **14. Drug dosage adjustment via run-to-run control**  
Good, R.; Hahn, J.; Edison, T.; Qin, S.J.;  
[American Control Conference, 2002. Proceedings of the 2002](#)  
Volume 5, 8-10 May 2002 Page(s):4044 - 4049 vol.5  
Digital Object Identifier 10.1109/ACC.2002.1024562  
[AbstractPlus](#) | Full Text: [PDF](#)(620 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **15. Expanding the capability of photo induced-emf arrays [nondestructive testing]**  
Dunning, G.J.; O'Meara, T.R.; Pepper, D.M.;  
[Lasers and Electro-Optics, 1999. CLEO '99. Summaries of Papers Presented at the Conference on](#)  
23-28 May 1999 Page(s):427 - 428  
Digital Object Identifier 10.1109/CLEO.1999.834404  
[AbstractPlus](#) | Full Text: [PDF](#)(240 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **16. Optimized in situ rinsing for HF last processes**  
Wolke, K.; Kubelbeck, A.; Cornelissen, I.; Meuris, M.; Oshinowo, J.;  
[Semiconductor Manufacturing Conference Proceedings, 1997 IEEE International Symposium on](#)  
6-8 Oct. 1997 Page(s):P95 - P98  
Digital Object Identifier 10.1109/ISSM.1997.664633  
[AbstractPlus](#) | Full Text: [PDF](#)(364 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **17. In-situ measurements of surface mount IC package deformations during reflow soldering**  
Pecht, M.G.; Govind, A.;  
[Components, Packaging, and Manufacturing Technology, Part C, IEEE Transactions on \[see also](#)  
[Components, Hybrids, and Manufacturing Technology, IEEE Transactions on\]](#)  
Volume 20, [Issue 3](#), July 1997 Page(s):207 - 212  
Digital Object Identifier 10.1109/3476.649442  
[AbstractPlus](#) | [References](#) | Full Text: [PDF](#)(276 KB) IEEE JPL  
[Rights and Permissions](#)
- 
- ☐ **18. Model-based control for chemical-mechanical planarization (CMP)**  
de Roover, D.; Emami-Naeini, A.; Ebert, J.L.;  
[American Control Conference, 2004. Proceedings of the 2004](#)  
Volume 5, 30 June-2 July 2004 Page(s):3922 - 3929 vol.5  
[AbstractPlus](#) | Full Text: [PDF](#)(864 KB) IEEE CNF  
[Rights and Permissions](#)

- ☐ **19. High thermal performance silicon heat spreaders with microwhisker structure**  
Hammel, E.; Nagl, C.; Nicolics, J.; Hanreich, G.;  
[Electronics Manufacturing Technology Symposium, 1999. Twenty-Fourth IEEE/CPMT](#)  
18-19 Oct. 1999 Page(s):426 - 432  
Digital Object Identifier 10.1109/IEMT.1999.804855  
[AbstractPlus](#) | Full Text: [PDF](#)(832 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **20. The reliability improvement on self-aligned contact CMOS by optimizing poly etching**  
Chang, C.-D.; Chu, C.-Y.; Lin, D.-E.;  
[Electronics Manufacturing Technology Symposium, 1998. Twenty-Third IEEE/CPMT](#)  
19-21 Oct. 1998 Page(s):136 - 138  
Digital Object Identifier 10.1109/IEMT.1998.731067  
[AbstractPlus](#) | Full Text: [PDF](#)(843 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **21. Robust run-to-run control for semiconductor manufacturing: an internal model control approach**  
Adivoklanu, S.; Zafriou, E.;  
[American Control Conference, 1998. Proceedings of the 1998](#)  
Volume 6, 24-26 June 1998 Page(s):3687 - 3691 vol.6  
Digital Object Identifier 10.1109/ACC.1998.703303  
[AbstractPlus](#) | Full Text: [PDF](#)(528 KB) IEEE CNF  
[Rights and Permissions](#)
- 
- ☐ **22. Model-based product quantity control**  
Ramakrishnan, V.; Walker, D.M.H.;  
[Electronics Manufacturing Technology Symposium, 1995. Manufacturing Technologies - Present and Future, Seventeenth IEEE/CPMT International](#)  
2-4 Oct. 1995 Page(s):389 - 395  
Digital Object Identifier 10.1109/IEMT.1995.526192  
[AbstractPlus](#) | Full Text: [PDF](#)(584 KB) IEEE CNF  
[Rights and Permissions](#)

[Help](#) [Contact Us](#) [Privacy & Security](#) [IEEE.org](#)

© Copyright 1997 IEEE - All Rights Reserved